概要

Overview

プロセス

システム SYSTEM

その他 Other

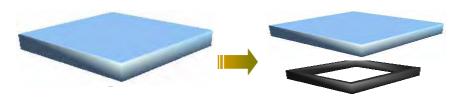


## AccuPell Phoenix D-PEL

## Pellicle Removal System

Application: Automatic residue free removal of pellicle from industry standard reticles (We can provide automatic, semi-automatic and manual type)

*In Brief:* The combination of pellicle frame and glue are removed together from the mask surface. The innovative application of thermal energy to maximize cohesive elements in the glue film assures adhesion to the pellicle frame during removal. Significantly reducing or eliminating post pellicle removal glue cleaning processes.



## **Pellicle Removing**



Fig.1 Existing Pellicle removing



Fig.2 AccuPell removing



Fig.3 Semi-auto system

## **Features and Benefits**

Feature	Benefit
Process temperature gradient	Ensure that glue remains preferentially attached to frame and detaches from mask – eliminates gross residue
Fully automated operation	<ul> <li>Eliminates risky manual handling of valuable masks</li> <li>Ensures clean, reliable, repeatable removal</li> <li>Operator-independent results</li> </ul>
Mask/Pellicle library	<ul> <li>Pre-loaded removal parameters for all industry standard mask dimensions and pellicle combinations</li> <li>Custom parameters easily programmable</li> </ul>
Choice of loader configurations	Adapts to SMIF, FOUP, Cassette or custom requirements

